

IN THE ABSTRACT:

Please replace the present Abstract of the Disclosure with the following:

a1 --An exposure apparatus includes an illumination optical system for illuminating an original with ultraviolet light, a projection optical system for projecting a pattern of the original onto a substrate to be exposed and a gas purging means for replacing an inside space, which contains optical components of at least one of the illumination optical system and the projection optical system, with a gas having substantially no water content.--.

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 1,

line 8, after "for" (second occurrence) insert
--the--;
line 17, after "as" insert --an--; and
line 27, after "in" insert --an--.

Page 2,

line 4, after "of" (first occurrence) insert
--the--;